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BIBDATASHEET

Bib Data Sheet

CONFIRMATION NO. 4623

| SERIAL NUMI 10/731,494 | | | CLASS 438 | GROUP ART UNIT 2823 | | UNIT | ATTORNEY DOCKET NO. AF01194 |
|--|--|--|--------------|------------------------|------------------------------|-------------|-----------------------------------|
| APPLICANTS . Arvind Halliyal, Cupertino, CA; | | | | | | | |
| Fred TK Cheung, San Jose, CA; Rinji Sugino, San Jose, CA;Hidehiko Shiraiwa, San Jose, CA; Tazrien Kamal, San Jose, CA; Jean Y. Yang, Sunnyvale, CA; | | | | | | | |
| ** CONTINUING DATA ********************************** | | | | | | | |
| ** FOREIGN APPLICATIONS ************************************ | | | | | | | |
| IF REQUIRED, FOREIGN FILING LICENSE GRANTED ** 03/10/2004 | | | | | | | |
| Foreign Priority claimed yes no State OR SHEETS TOTAL conditions met Verified and Allowance Verified and Acknowledged Examiner's Signature Initials CA 5 20 | | | | | | INDEPENDENT | |
| | | | | | | | CLAIMS 3 |
| ADDRESS 45305 RENNER, OTTO, BOISSELLE & SKLAR, LLP (AMDS) 1621 EUCLID AVE - 19TH FLOOR CLEVELAND , OH 44115-2191 | | | | | | | |
| TITLE Process for fabrication of spacer layer with reduced hydrogen content in semiconductor device | | | | | | | |
| FEES: Authority has been given in Paper No to charge/credit DEPOSIT ACCOUNT No for following: | | | | | All Fees 1.16 Fees (Filing) | | |

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